

angle to the axial direction, wherein the gas outlets are located in the axial distal end surface of the gas injector body.

Please add new Claims 37-40 as follows:

37. (New) The gas injector of Claim 25, wherein the distal end of the gas injector body is substantially planar.

38. (New) The gas injector of Claim 25, wherein all of the gas outlets supply process gas through the distal end of the gas injector body.

39. (New) A gas injector for supplying process gas to a plasma processing chamber wherein a semiconductor substrate is subjected to plasma processing, the gas injector comprising:

gas injector body sized to extend through a chamber wall of the processing chamber such that a distal end of the gas injector body is exposed within the processing chamber, the gas injector body including a plurality of gas outlets adapted to supply process gas into the processing chamber;

an annular flange adapted to overlie and contact an outer surface of the chamber wall; and

a first O-ring seal in a surface of the flange for sealing against the outer surface of the chamber wall.

40. (New) The gas injector of Claim 39, comprising a second O-ring seal on an outer surface of the gas injector body.